



NEUTRONIX-QUINTEL CORPORATION

Neutronix-Quintel (NXQ) is a leading provider of microlithography equipment for the Opto-electronic, Microsystem and Nanotechnology markets. Our unique history gives us critical experience and expertise in equipment engineering and allows us to consistently deliver high quality, reliable solutions, especially, at a highly competitive price. Equally as important, we are a full service manufacturer, providing our customers with a single source for training, equipment maintenance and parts replacement. Focus on customer satisfaction is our formula for success!



MPA 500 / 600 Series Mask Aligners

- Projection Alignment - 72 WPH
- Temperature Control
- Thermal/Pneumatic Distortion Control
- 1X Scanning
- Mask Changer (Optional)
- Wafer Sizes: 3" to 6" Semi Spec
- Wafer Feed: Dual Cassette, Auto Feeder
- Alignment: Manual/Automatic
- Resolution: 1.5um CD with Depth-Of-Focus +/- 6um



PLA 501 / 600 Series Mask Aligner

- Contact/Proximity Alignment - 60-100 WPH
- Infrared Backside Alignment
- Dual Channel Light Integration or C.I.
- Fiber Optic Illumination
- High Resolution Video
- Wafer Sizes: 2" to 6" Semi Spec, Pieces, Squares
- Wafer Feed: Manual and/or Cassette to Cassette Auto Feeder
- Alignment: Manual / Automatic
- UV Power: 250, 350, 500 Watts, 1 and 2 Kilo Watts
- UV Spectrum: Deep UV, NEAR Deep UV, Near UV
- Resolution: Less Than .5um in Hard Contact



Automated Pattern Recognition Alignment System

NeuVision² combines our wealth of PLA experience with user-friendly software to create an alignment system that easily adapts to a broad range of application challenges. With NeuVision installed on your PLAs, you can:

- Automatically align on irregular wafer surfaces such as metal layers or other noisy or low return thin films.
- Define your own alignment marks. While the Chevron Scheme can be used, it is not required for automatic alignment significantly increasing the capture area and eliminating the cost of retooling masks.
- Program alignment tolerances to match production goals. Extremely tight alignment, 1 um 3 sigma, can be achieved reliably, throughput can be increased by relaxing tolerance specifications.
- Reduce wafer to mask contacts and decrease defect densities associated with resist lift off.
- Dramatically improves system ergonomics.



Q4000-4 Mask Aligner

- Substrate size from pieces to 100 mm diameter
- Manual X, Y and theta alignment stage
- Vacuum / Pressure Contact Exposure Modes
- Manual trayloading feature
- Splitfield / Singlefield optical microscope
- Simple, topside mask loading
- User friendly
- Low maintenance

Available Options:

- Infrared (IR) back side alignment
- UV / NUV exposure optics
- Carousel loading
- CCTV Viewing



Q4000-6 Mask Aligner

- Substrate size from pieces to 150 mm diameter
- Manual X, Y and theta alignment stage
- Vacuum / Pressure contact exposure modes
- Optical Splitfield and CCTV microscope options
- Simple, topside mask loading
- User friendly
- Low maintenance

Available Options:

- Infrared (IR) back side alignment
- Large gap alignment
- UV / NUV / DUV exposure optics
- Carousel loading



Q7500 Mask Aligner

- Multiple contact & proximity exposure modes
- Wafer size from pieces to 200 mm diameter
- Square substrate up to 7x7
- Optical and CCTV splitfield microscope options
- Simple topside mask loading
- Manual tray loading feature

Modular design, easily configurable for wide variety of applications with available options:

- Robotic autoloading handling
- Automatic alignment
- Optical (OBS) and Infrared (IR) backside alignment
- Large gap alignment
- UV / NUV / DUV Exposure optics



Q1200 Flood Expose System

A unique machine with single and double-sided exposure capability. Designed specifically for single mask level applications and/or gross geometries and non-critical alignment - current applications include power devices, LEDs and MEMs applications.

- R&D and production applications
- Manual loading of substrates
- Single-side and double-side exposure capability
- Small pieces to 200 mm diameter substrate size

Available Options:

- CCTV Microscope
- Manual X, Y, and theta alignment stage



Vietnam's leading supplier of semiconductor interconnect assembly equipment.

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